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	Application No.	Applicant(s)	
Netice of Allered With	09/769,812	LIN ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Lan_Vinh	1765	
The MAILING DATE of this communication app. All claims being allowable, PROSECUTION ON THE MERITS I herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED in 5) or other appropriate communication is second RIGHTS. This application is second in the communication is second in the communication in the communic	n this application. If not included unication will be mailed in due co	i ourse <b>THIS</b>
1.   This communication is responsive to   Amendment filed of	1 12/22/2003.		
2. The allowed claim(s) is/are 11 and 13-18.			
3. $\boxtimes$ The drawings filed on <u>26 January 2001</u> are accepted by			
<ul> <li>4. ☐ Acknowledgment is made of a claim for foreign priority</li> <li>a) ☐ All b) ☐ Some* c) ☐ None of the:</li> </ul>	under 35 U.S.C. § 119(a)-(d)	or (f).	
<ol> <li>Certified copies of the priority documents had</li> </ol>	ve been received.		
<ol><li>Certified copies of the priority documents had</li></ol>			
<ol><li>Copies of the certified copies of the priority of</li></ol>	locuments have been received	d in this national stage application	n from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
<ol> <li>Acknowledgment is made of a claim for domestic priority reference was included in the first sentence of the specifi</li> </ol>	cation or in an Application Dat	ta Sheet. 37 CFR 1.78.	specific
(a) ☐ The translation of the foreign language provisional			
<ol> <li>Acknowledgment is made of a claim for domestic priority in the first sentence of the specification or in an Application</li> </ol>	under 35 U.S.C. §§ 120 and/o on Data Sheet. 37 CFR 1.78.	or 121 since a specific reference	was included
Applicant has THREE MONTHS FROM THE "MAILING DATE" below. Failure to timely comply will result in ABANDONMENT o	of this communication to file a of this application. THIS THR	reply complying with the require EE-MONTH PERIOD IS NOT E	ements noted XTENDABLE.
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be sub- INFORMAL PATENT APPLICATION (PTO-152) which gi</li> </ol>	mitted. Note the attached EXA ves reason(s) why the oath or	MINER'S AMENDMENT or NO declaration is deficient.	TICE OF
<ol> <li>CORRECTED DRAWINGS ( as "replacement sheets") metalong including changes required by the Notice of Draftspe</li> <li>□ hereto or 2) □ to Paper No</li> </ol>		√ ( PTO-948) attached	
(b) ☐ including changes required by the proposed drawing	correction filed which	has been approved by the Eva	miner
(c) ☐ including changes required by the attached Examine			
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on th	e drawings in the front (not the ba	
9. ☐ DEPOSIT OF and/or INFORMATION about the depattached Examiner's comment regarding REQUIREMENT FOR	osit of BIOLOGICAL MATE THE DEPOSIT OF BIOLOGIC	RIAL must be submitted. Not CAL MATERIAL.	te the
Attachment(s)			
I□ Notice of References Cited (PTO-892)	5☐ Notice of Info	rmal Patent Application (PTO-15	52)
2 Notice of Draftperson's Patent Drawing Review (PTO-948)		nmary (PTO-413), Paper No	
Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No	<sup>18),</sup> 7∐ Examiner's A	mendment/Comment	
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8⊠ Examiner's S 9⊡ Other .	tatement of Reasons for Allowar	ıce
		Lan Vinh AU 176 <b>∯</b>	
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U.S. Patent and Trademark Office PTOL-37 (Rev. 11-03) Application/Control Number: 09/769,812

Art Unit: 1765

## Allowable Subject Matter

1. Claims 11, 13-18 allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claim 11, the cited prior art of record fails to disclose a method of etching a low-k dielectric layer comprises the step of etching an organic low-k dielectric layer formed over an insulation layer by applying a plasma power and flowing NH3 and H2 and O2/CO2 gases. The closest cited prior art of Ye et al (US 6,458,516) suggests etching an organic low-k dielectric layer by gaseous plasma using NH3 and N2 and O2 gases (col 22, lines 11-15)

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 571 272 1471. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571 272 1465. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703 308-0661.

LV

January 15, 2004